U.S.N. 10/050,322

1756 DEV

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Ming Huan Tsai

Group Art Unit: 1756

Serial No.: 10/050,322

Examiner: Nicole M. Barreca

Filed: 01/15/2002

In Response to Office Action

Dated: 12/16/2004

For: A BI-LAYER PHOTORESIST DRY DEVELOPMENT AND

REACTIVE ION ETCH METHOD

Attorney Docket No.: 67,200-613

Certificate of Mailing

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents P.O. box 1450, Alexandria, Va 22313-1450.

Date: Feb. 15, 2005

RESPONSE OF OFFICE ACTION RE-OPENED PROSECUTION

Commissioner for Patents P.O. Box 1450 Alexandria, Va 22313-1450

Dear Sir:

In response to an Office Action mailed 12/16/2004 please consider the following remarks.